

## **Reference Generator for Multilevel Nonlinear Resistivity Memory Storage Elements**

### **Background of the Invention**

#### **Field of the Invention**

5 [0001] This invention relates generally to electrical circuits for the generation of reference currents and/or voltages. More particularly, this invention relates to electrical circuits for the generation of multiple reference currents and/or voltages for non-linear resistive elements such as magnetic tunneling junctions (MTJ). Further, this invention relates to electrical circuits for the generation of multiple  
10 reference currents and/or voltages to provide the reference levels for the sensing of multiple bits of digital data stored within a Magnetic Random Access Memory (MRAM) cell.

#### **Description of Related Art**

[0002] Magneto-electronic memories are emerging as important memory  
15 technologies. Presently, there are three types of magnetic memory devices that are grouped according to the physics of their operation. These categories are a hybrid ferromagnetic semiconductor structure, a metal spin transistor or spin valve, and a magnetic tunnel junction (MTJ). Writing to memories of each of the devices is essentially the same because the direction of a magnetic field  
20 determines the state of the digital data stored in a memory cell. However, reading each of the devices is different. The ferromagnetic semiconductor

device essentially employs a Hall Effect to determine the state of the digital data stored in the memory cell. The metal spin transistor and the magnetic tunnel junction each employ a change in magneto-resistance to determine a state of the digital data stored in the memory cell. In a metal spin transistor, the relative resistance difference is approximately from 6% to 8%. The discrimination of the state of the digital data is difficult with the metal spin transistor. However, the MTJ has a resistance difference approximately 12%.

[0003] As shown in Fig. 1, a memory array **5** is generally formed of groups of MTJ cells **10** in columns and rows. Each MTJ cell **10** has an MTJ device **15** for retaining digital data as an orientation of the magnetic fields within the MTJ device **15**. A sense voltage  $V_{\text{cell}}$  **20** is applied to a selected MTJ cell **15**. The application of the sense voltage  $V_{\text{cell}}$  **20** causes a cell current  $I_{\text{cell}}$  **25** to flow through the MTJ device **15**. The magnitude of the cell current  $I_{\text{cell}}$  **25** is dependent on the resistance of the MTJ device **15**, which is dependent on the orientation of the magnetic fields of the MTJ device **15**.

[0004] The cell current  $I_{\text{cell}}$  **25** flows through the cell load resistor **30** to develop the sense voltage  $V_{\text{sense}}$  **80**, which is the input to the comparator **55**. The sense voltage  $V_{\text{sense}}$  **80** is compared within the comparator **55** with the reference voltage  $V_{\text{REF}}$  **75** to determine the state of the digital data retained within the MTJ device **15**. Ideally, the voltage  $V_{\text{REF}}$  **75** has a magnitude that is approximately the average of the sense voltage  $V_{\text{sense}}$  **80** with the MTJ device **15** at its maximum resistance ( $R_{\text{max}}$ ) and the sense voltage  $V_{\text{sense}}$  **80** with the MTJ device **15** at its

minimum resistance ( $R_{min}$ ). The average of the sense voltage  $V_{sense}$  80 with the MTJ device 15 at its maximum resistance ( $R_{max}$ ) and the sense voltage  $V_{sens}$  80 with the MTJ device 15 at its minimum resistance ( $R_{min}$ ) is dependent upon the expression:

$$V_{sense} \propto \frac{1}{2}(R_{min} + R_{max})$$

[0005] A reference current source 35 generates the reference current  $I_{REF}$  45 as function of the a biasing voltage 40 that is approximately twice the magnitude of the sense voltage  $V_{cell}$  20 applied across two pair of serially connected reference resistance devices 36, 37, 38, and 39. The reference resistance devices 36, 37, 38, and 39 are MTJ devices that have their magnetic orientations set such that the reference resistance devices 36 and 38 have their resistance set to the minimum resistance values and the reference resistance devices 37 and 39 set to their maximum resistance values. It can be shown that the reference current  $I_{REF}$  45 becomes the current generated by sense voltage  $V_{cell}$  20 applied to a resistor that has an average value of the maximum resistance and the minimum resistance of the MTJ device 15.

[0006] However, it is apparent that the voltage  $V_2$  across the reference resistance devices 37 and 39 are greater than the voltage  $V_1$  across the reference resistance devices 36 and 38. The resistance of the MTJ devices 36, 37, 38, and 39 is not linear, as is shown in Fig. 2. Fig. 2 shows the biasing voltage dependence of the magneto-resistance (MR) ratio. The MR ratio is defined as the difference in resistance between the two states divided by the

resistance in the low state expressed as a percentage. As shown, the voltage dependence indicates that the reference MTJ devices **36** and **38** are biased at the voltage level **V1 65** and the reference MTJ devices **37** and **39** are biased at the voltage level **V2 70** and that they are not really equal to the sense voltage **V<sub>cell</sub> 20**. The reference MTJ devices **36**, **37**, **38**, and **39** do not really have their maximum and minimum resistances equal to the values of the respective maximum and minimum resistance of the MTJ device **15**. The equivalent resistance of the reference resistance devices **36**, **37**, **38**, and **39** as configured is not equal to  $\frac{1}{2}(R_{\min} + R_{\max})$ . This causes the reference current **I<sub>REF</sub> 45** to be unequal to the average between the cell current **I<sub>cell</sub> 25** with the MTJ device **15** at a maximum resistance (**R<sub>max</sub>**) and the cell current **I<sub>cell</sub> 25** with the MTJ device **15** at a minimum resistance (**R<sub>min</sub>**).

[0007] "Demonstration of a Four State Sensing Scheme for a Single Pseudo-Spin Valve GMR Bit", Zhang et al., IEEE Transactions on Magnetism, Volume: 35, Issue: 5, Sep 1999, describes a simple and fast method for sensing four states from a single Pseudo-Spin Valve GMR device.

[0008] "Windowed MRAM Sensing Scheme", Zhang, et al., "Memory Technology, Records of the 2000 IEEE International Workshop on Design and Testing," August 2000, pp.: 47-55 details a method for allowing bits with unstable domains to be detected during reading. The method also allows for an improved sensing error rate by identifying read cycles with inadequate signal size caused for example by external noise.

[0009] "A Novel Sensing Scheme for an MRAM with a 5% MR ratio", Yamada, et al., "Digest of Technical Papers. 2001 Symposium on VLSI Circuits," June, 2001, pp.: 123-124 provides a novel sensing scheme for a magneto-resistive random access memory (MRAM) with a twin cell structure. It operates by sensing the difference in voltage between a couple of magnetic tunnel junctions (MTJ) in a transitional state.

[0010] "Fully Integrated 64 Kb MRAM with Novel Reference Cell Scheme", Jeong, et al., "Digest. International Electron Devices Meeting - IEDM '02", December, 2002, pp.: 551- 554, employs a new sensing scheme with a separated half-current source. The separated half current source is adopted for the reference bit line to increase the sensing signal.

[0011] U. S. Patent 6,317,376 (Tran, et al.) and U. S. Patent Application 2001/0053104 (Tran, et al.) describe a Magnetic Random Access Memory ("MRAM") device. The MRAM device includes an array of memory cells and generates reference signals that can be used to determine the resistance states of each memory cell in the array, despite variations in resistance due to manufacturing tolerances and other factors such as temperature gradients across the array, electromagnetic interference and aging.

[0012] U. S. Patent 6,055,178 (Naji) teaches an MRAM device that includes a memory array and a reference memory array. Each reference memory cell has a magnetic memory cell and a transistor, that is coupled in series and has a reference resistance across the reference memory cell and the transistor. The

transistor is controlled by a reference row line control, so as for the reference resistance to show a mid-value between the maximum resistance and the minimum resistance of the magnetic memory cell. A bit line current ( $I_b$ ) and a reference bit current ( $I_r$ ) are provided to the magnetic memory cell and the reference memory cell, respectively. Magnetic states alternate the bit line current, which is compared to the reference bit current to provide an output.

[0013] U. S. Patent 6,169,689 (Naji) illustrates an MTJ stacked cell memory sensing method and apparatus. The memory array consists of stacks of cells in an addressable array with each stack including MTJ memory cells stacked together with current terminals connected in series, and including a first and second current terminals coupled through an electronic switch to a current source. Each stack includes  $2^n$  levels of memory. A voltage drop across an addressed stack is sensed. Reference voltages equal to the  $2^n$  memory levels are provided and the sensed voltage drop is compared to the reference voltages to determine the memory level in the addressed stack. Encoding apparatus is used to convert the voltage drop to a digital output signal.

[0014] U. S. Patent 6,385,109 (Naji) and U. S. Patent 6,496,436 (Naji) detail readout circuitry for a magnetic tunneling junction (MTJ) memory cell, or an array of MTJ memory cells, which require a varying reference voltage equal to  $(V_{bias1}/2)(1+R_{min}/R_{max})$ . The  $V_{bias1}$  is a clamping voltage applied to the readout circuitry,  $R_{min}$  is a minimum resistance of the magnetic tunneling junction memory cell, and  $R_{max}$  is a maximum resistance of the magnetic tunneling junction memory cell. A

reference voltage generator generates the reference voltage and includes an operational amplifier and two MTJ memory cells connected to provide an output signal equal to  $(V_{bias1}/2) (1+R_{min}/R_{max})$ .

[0015] U. S. Patent 6,426,907 (Hoenigschmid) describes a reference circuit for an MRAM array, including logic "1" reference MRAM cells and coupled in parallel with logic "0" reference MRAM cells. The reference current is coupled to a measurement resistor of a sense amplifier, which is adapted to determine the logic state of an unknown memory cell.

[0016] U. S. Patent 6,445,612 (Naji) specifies an MRAM with midpoint generator reference and method for readout. The MRAM includes a data column of memory cells and a reference column, including a midpoint generator, positioned adjacent the data column on a substrate. The memory cells and the midpoint generator include similar magneto-resistive memory elements, e.g. MTJ elements. The MTJ elements of the generator are each set to one of  $R_{max}$  and  $R_{min}$  and connected together to provide a total resistance of a midpoint between  $R_{max}$  and  $R_{min}$ . A differential read-out circuit is coupled to the data column and to the reference column for differentially comparing a data voltage to a reference voltage.

## Summary of the Invention

[0017] An object of this invention is to provide a reference generator with multiple reference levels.

[0018] Another object of this invention is to provide a reference generator that proportionally tracks nonlinear resistive elements.

[0019] To achieve at least one of these objects, a multilevel reference generator has a plurality of standard resistive elements such as multilevel magnetic tunnel  
5 junctions set to differing parallel and anti-parallel magnetic orientations. Each resistive element is biased at a constant level to impart a resultant level from each resistive element. If the constant level is a constant voltage, the resultant levels of the plurality of resistive elements and the mirrored replications are currents. Alternately, the constant level is a constant current and the resultant  
10 levels of the plurality of resistive elements and the mirrored replications are voltages. Further, each resistive element has a resistance different from the resistance of each of the plurality of resistive elements.

[0020] The multilevel reference generator has a plurality of mirror sources. Each mirror source is in communication with the one of the plurality of resistive  
15 elements such that each mirror source receives the resultant level from the one standard resistive element and provides a mirrored replication of the resultant level.

[0021] The multilevel reference generator has a plurality of reference level combining circuits. Each reference level combining circuit is connected to  
20 receive a first mirrored replication of one resultant level from one mirror source and a second mirrored replication of the resultant level from a second mirror source. From a combination of the one mirrored replication from the one mirror



source and the second mirrored replication from the second mirror source each reference level combining circuit creates one of the reference levels.

[0022] The reference level combining circuit includes a summing circuit to additively combine the first and second mirrored replication and a scaling circuit to create a scaling of the combined first and second mirrored replications. This creates a reference level. The reference level maybe a reference current. In the alternative, the reference level is a voltage developed across a reference resistor with the reference current flowing through the reference resistor. Therefore, the reference generator may include a plurality of reference resistors. Each reference resistor associated with one of the plurality of reference level combining circuits to receive the reference current for creation of the voltage that is the reference level.

### **Brief Description of the Drawings**

[0023] Fig. 1 is a schematic diagram representing an MRAM array with the sense amplifier reference generator of the prior art.

[0024] Fig. 2 is a plot of the magneto-resistance factor of an MTJ memory cell versus a biasing voltage of the prior art.

[0025] Fig. 3 is a schematic diagram illustrating a multilevel MTJ memory cell.

[0026] Fig. 4 is a plot illustrating the multiple current levels available from the multilevel MTJ memory cell of Fig. 3.

[0027] Fig. 5 is a schematic diagram of the reference or standard resistances and the current mirror source of this invention illustrating the constant biasing of the standard resistances.

[0028] Fig. 6 is a schematic diagram of the current combining circuit to generate the reference current of this invention.

[0029] Fig. 7 is a schematic diagram of the reference generator for generating a reference voltage of this invention.

[0030] Fig. 8 is a schematic diagram of one of the voltage reference generators of the multilevel voltage reference generator of this invention.

[0031] Fig. 9 is a schematic diagram of an MRAM memory array including the multilevel reference voltage generator and sense amplifier of this invention.

[0032] Figs. 10a - 10d are schematic diagrams illustrating the magnetic orientation of MTJ devices employed as the reference or standard resistances of this invention.

## Detailed Description of the Invention

[0033] Referring to Fig. 3, a multilevel MTJ cell **105** in an MRAM memory array **100** consists of two MTJ devices **110** and **115** and a gating transistor **120**. The bit line **125** provides a biasing voltage to generate a read current  $I_{RD}$  **145** through the two MTJ devices **110** and **115**. The word line **130** provides the control signal to activate the gating transistor **120** during either the programming (writing) or

reading of the multilevel MTJ cell **105**. The primary program line **135** is connected to the source of the gating transistor **120**. The second program line **140** is connected to the MTJ device **110**. The third program line **142** is connected to the MTJ device **115**. The second program line **140** and the third program line **142** provide the programming currents necessary to determine the orientation of the magnetic fields of the two MTJ devices **110** and **115**. The primary program line **135** provides the necessary source/return path for these programming currents.

[0034] The multilevel memory cell **105**, when programmed, contains two bits of digital data or four different states. The MTJ device **110** is sized to have differing maximum and minimum resistivity than that of the MTJ device **115**. Thus, if the MTJ device **110** and the MTJ device **115** are both programmed to have parallel orientations, the multilevel MTJ cell **105** has a cell resistance state that is the minimum total resistance. Alternately, if the MTJ device **110** and the MTJ device **115** are both programmed to have anti-parallel orientations, the multilevel MTJ cell **105** has a cell resistance state that is the maximum total resistance. If the MTJ device **110** and the MTJ device **115** are both programmed to have opposite (one parallel and one anti-parallel) orientations, the multilevel MTJ cell **105** has two resistance states that are between the maximum and minimum resistance.

[0035] For a read operation, the bit line **125** is set to a constant biasing voltage for generation of the read current  $I_{RD}$  **145**. The primary program line **135** is connected to provide a path for the flow of the read current  $I_{RD}$  **145** for sensing.

During the read operation, the word line is activated to turn on the gating transistor **120** to connect the two MTJ devices **110** and **115** to the primary program line **135**.

[0036] The read current  $I_{RD}$  **145** is transferred to a sense amplifier that must now distinguish between the four different levels of read current  $I_{RD}$  **145**. A multilevel reference source must provide separate references that are ideally midway between the levels of current of the read current  $I_{RD}$  **145** so as to distinguish the four levels of the read current  $I_{RD}$  **145**. Referring now to Fig. 4, the representation of the four cell resistance states will generate the four read currents  $I_{RD1}$  **150a**,  $I_{RD2}$  **150b**,  $I_{RD3}$  **150c**, and  $I_{RD4}$  **150d**. The multilevel reference source must provide reference currents  $I_{REF1}$  **155a**,  $I_{REF2}$  **155b**, and  $I_{REF3}$  **155c** that have magnitudes that are midway between the magnitudes of the four read currents  $I_{RD1}$  **150a**,  $I_{RD2}$  **150b**,  $I_{RD3}$  **150c**, and  $I_{RD4}$  **150d**.

[0037] The fundamental circuits that form the multilevel reference generator of this invention are shown in Figs. 5 and 6. The multilevel reference generator has a nonlinear resistive element **200** for each of the reference levels provided by the multilevel reference generator. The nonlinear resistive element **200** is biased to a constant voltage level  $V_A$  **220** to generate the current  $I_n$  **235**. The nonlinear resistive element **200** in the preferred embodiment consists of two MTJ devices **205** and **210**. The two MTJ devices **205** and **210** are connected in parallel and attached between the constant voltage level  $V_A$  **220** and the substrate biasing voltage  $V_{ss}$ . The two MTJ devices **205** and **210** are programmed to have their

orientation of the magnetic fields as shown in Figs. 10a – 10d. The orientation of the magnetic fields of the two MTJ devices **205** and **210** determine the total resistance of the resistance of the nonlinear resistive element **200**. In Fig. 10a, the orientation of the magnetic fields is set to be anti-parallel and the resistance of the nonlinear resistive element **200** is set to the maximum resistance and the current  $I_n$  **235** is at its minimum or equivalent to the read current  $I_{RD4}$  **150d** of Fig. 4. In Fig. 10b, the orientation of the magnetic field of the MTJ device **205** is set to be anti-parallel such that its resistance is at the maximum and the MTJ device **210** is set to be parallel such that its resistance is at the minimum. This makes the resistance of the nonlinear resistive element **200** such that the current  $I_n$  **235** is at an intermediate level that is equivalent to the read current  $I_{RD3}$  **150c** of Fig. 4. In Fig. 10c, the orientation of the magnetic field of the MTJ device **205** is set to be parallel such that its resistance is at the minimum and the MTJ device **210** is set to be anti-parallel such that its resistance is at the maximum. This makes the resistance of the nonlinear resistive element **200** such that the current  $I_n$  **235** is at an intermediate level that is equivalent to the read current  $I_{RD2}$  **150b** of Fig. 4. In Fig. 10d, the orientation of the magnetic fields is set to be parallel and the resistance of the nonlinear resistive element **200** is set to its minimum resistance and the current  $I_n$  **235** is at its maximum or equivalent to the read current  $I_{RD1}$  **150a** of Fig. 4.

[0038] Returning to Fig. 5, the source of the biasing transistor **225** is connected to establish the constant voltage level  $V_A$  **220**. The gate of the biasing transistor **225** is connected to a biasing voltage source  $V_{BIAS}$  **230**, thus establishing the

constant voltage level  $V_A$  220 as the voltage level of the biasing voltage source  $V_{BIAS}$  230 plus the threshold voltage ( $V_t$ ) of the biasing transistor 225. The current  $I_n$  235 is then determined by the formula:

$$I_n = \frac{(V_A)}{(R_{MTJ1} + R_{MTJ2}) / R_{MTJ1} R_{MTJ2}}$$

5 [0039] The MOS transistors **M3 240** and **M4 245** are connected as a current mirror source. The gates of the MOS transistors **M3 240** and **M4 245** are connected together and to the drain of the biasing transistor 225 such that the current  $I_n$  235 flows through the MOS transistor **M3 240**. The mirror current  $I_n$  **MIRROR 250** is source from the source of the MOS transistor **M4 245**.

10 [0040] The multilevel reference generator of this invention will have a resistive element as will the current mirror formed by the MOS transistors **M3 240** and **M4 245** for each of the four read currents  $I_{RD1}$  150a,  $I_{RD2}$  150b,  $I_{RD3}$  150c, and  $I_{RD4}$  150d of Fig. 4. The structure of the nonlinear resistive element 200 is equivalent to that of the multilevel MTJ cell 105 of Fig. 3. The equivalent structure and the  
15 constant voltage level  $V_A$  220 ensure that the mirror currents  $I_n$  235 are approximately equal to the read currents  $I_{RD}$  145.

[0041] To generate the reference currents  $I_{REF1}$  155a,  $I_{REF2}$  155b, and  $I_{REF3}$  155c of Fig. 4, the multilevel reference generator combines two of the mirrored current and effectively averages the combined sum to form one of the reference  
20 currents. Referring to Fig. 6, the drain of the MOS transistors **M5 260** is

connected to receive two of the mirrored currents  $I_n$  250 and  $I_{n+1}$  255. The MOS transistors **M5 260** and **M6 265** are connected as a current source. In the preferred embodiment the MOS transistors **M5 260** and **M6 265** are scaled in size such that the reference current  $I_{REF\_n}$  270 is determined by the formula:

$$I_{REF\_n} = \frac{(I_n + I_{n+1})}{sf}$$

where:

**sf** is a scaling factor that in the preferred embodiment is two (2) to achieve the midpoint between the two mirrored currents  $I_n$  250 and  $I_{n+1}$  255.

[0042] The reference current  $I_{REF\_n}$  270 may be applied directly to the sense amplifier as a reference current. Alternately, as shown in Fig. 8, the reference current  $I_{REF\_n}$  270 of the reference current generator 275 may be applied within the multilevel reference generator of this invention to a reference resistor 280. The voltage across the reference resistor 280 then becomes the reference voltage  $V_{REF\_n}$ .

[0043] Fig. 7 illustrates the whole reference generation sub-circuit 300 necessary to provide one of the reference levels of a multilevel reference generation circuit of this invention. The reference generation sub-circuit 300 as shown creates the first reference voltage  $V_{REF\_1}$  380 that is developed from the reference current  $I_{REF\_1}$  370. The reference generation sub-circuit 300 includes a first nonlinear

resistive element **305**. The first nonlinear resistive element **310** is formed by combining two MTJ devices **307** and **309** connected in parallel. The two MTJ devices **307** and **309** have their magnetic fields set to be parallel. This makes the resistance level of the two MTJ devices **307** and **309** at their minimum values and any current through them at the maximum value when they are biased at a constant voltage level  $V_A$  **315**.

[0044] The biasing transistor **325** has its gates set to a biasing voltage  $V_{BIAS}$  to set the constant voltage level  $V_A$  **315** at the constant level of  $V_{BIAS}$  plus the threshold voltage level  $V_T$  of the biasing transistor **325**. The resultant current  $I_1$  **320** flowing through the two MTJ devices **307** and **309** is approximately equivalent to the first read current level  $I_{RD1}$  of Fig. 4.

[0045] A first mirror source **330** is connected to provide the resultant current  $I_1$  **320** and a first mirrored replication current  $I_{1MIRROR}$  **335** of the resultant current  $I_1$  **320**. The first mirror source by connecting the MOS transistors **332** and **334** such that their gates connected together and to the drain of the biasing transistor **325** and the drain of the MOS transistor **332**. The first mirrored replication current  $I_{1MIRROR}$  **335** flows from the drain of the MOS transistor **334**.

[0046] The reference generation sub-circuit **300**, further, includes a second nonlinear resistive element **310**. The second nonlinear resistive element **310** is formed of two MTJ devices **312** and **314** connected in parallel. The two MTJ devices **312** and **314** have their magnetic fields set to be such that the MTJ device **312** is parallel and the MTJ device **314** is anti-parallel. This makes the



resistance level of the MTJ device **312** at its maximum value and the MTJ device **314** at its minimum value and any current through them at an intermediate value when they are biased at a constant voltage level  $V_A$  **315**.

[0047] The biasing transistor **350** has its gates set to a biasing voltage  $V_{BIAS}$  to set the constant voltage level  $V_A$  **340** at the constant level of  $V_{BIAS}$  plus the threshold voltage level  $V_T$  of the biasing transistor **350**. The resultant current  $I_2$  **345** flowing through the two MTJ devices **312** and **314** is approximately equivalent to the second read current level  $I_{RD2}$  of Fig. 4.

[0048] A second mirror source **355** is connected to provide the resultant current  $I_2$  **350** and a second mirrored replication current  $I_2$ **MIRROR** **360** of the second resultant current  $I_2$  **345**. The second mirror source **355** is formed of the MOS transistors **357** and **359** having their gates connected together and to the drain of the biasing transistor **350** and the drain of the MOS transistor **357**. The second mirrored replication current  $I_2$ **MIRROR** **360** flows from the drain of the MOS transistor **359**.

[0049] A reference level combining circuit **365** is connected to receive the first mirrored replication current  $I_1$ **MIRROR** **335** from the first mirror source **330** and the second mirrored replication current  $I_2$ **MIRROR** **360** from the second mirror source **355**. A combination current of the first mirrored replication current  $I_1$ **MIRROR** **335** and the second mirrored replication current  $I_2$ **MIRROR** **360** creates the reference current  $I_{REF\_1}$  **370**. The reference level combining circuit **365** is formed by the MOS transistors **M5** **367** and **M6** **369** which form a current

source. The MOS transistors **M5 367** and **M6 369** are scaled such that the reference current  $I_{REF\_1}$  **370** is at the midpoint of the level of the first mirrored replication current  $I_1$ **MIRROR 335** and the level of the second mirrored replication current  $I_2$ **MIRROR 360** as described above. In the preferred embodiment, the scaling of the MOS transistors **M5 367** and **M6 369** is a factor of two to provide the averaging of the first mirrored replication current  $I_1$ **MIRROR 335** and the second mirrored replication current  $I_2$ **MIRROR 360**.

[0050] If the reference level of the multilevel generator is to be the reference voltage  $V_{REF\_1}$  **380**, then the resistor  $R_1$  **375** is provided such that the reference current reference current  $I_{REF\_1}$  **370** flows through the resistor  $R_1$  **375** to develop the reference voltage  $V_{REF\_1}$  **380**.

[0051] Refer now to Fig. 9 for a discussion of the structure and operation of an MRAM utilizing a reference generator of this invention. The MRAM contains a memory array **100** having rows and columns of multilevel MTJ cells **105** as is described in Fig. 3. Bit lines **125** of columns of the multilevel MTJ cells **105** are connected to the biasing transistor such that the voltage  $V_A$  **447** is a constant voltage equal to the constant level of  $V_{BIAS}$  plus the threshold voltage level  $V_T$  of the biasing transistor **435**. The voltage  $V_{BIAS}$  is the same biasing voltage that establishes the constant voltage  $V_A$  **220** of Fig. 5. The word line **130** is set to turn on the transistor **120**. The primary program **135** is connected such that it is set to the substrate voltage source  $V_{ss}$ . The cell current  $I_{CELL}$  **445** flows through the MTJ devices **110** and **115** to primary program line **135**. The magnitude of the

cell current  $I_{\text{CELL}}$  445 is determined by the magnetic orientation of the MTJ devices 110 and 115 and is equal to the four read currents  $I_{\text{RD1}}$  150a,  $I_{\text{RD2}}$  150b,  $I_{\text{RD3}}$  150c, and  $I_{\text{RD4}}$  150d of Fig. 4. The cell current  $I_{\text{CELL}}$  445 flows through the load resistor  $R_L$  440 to develop the cell voltage  $V_{\text{CELL}}$  442. The cell voltage  $V_{\text{CELL}}$  442 is applied to the comparators 450, 455, and 460. The cell voltage  $V_{\text{CELL}}$  442 is compared in the comparators 450, 455, and 460 to the reference voltages  $V_{\text{REF}_1}$  465,  $V_{\text{REF}_2}$  470, and  $V_{\text{REF}_3}$  475 to derive the digital data contents of the memory cell 105. The outputs of the comparators 450, 455, and 460 provide a barometer code that is interpreted by the barometer coder 480 to develop the digital data bits  $b_0$  485 and  $b_1$  490.

[0052] The reference generator 400 is connected to provide the reference voltages  $V_{\text{REF}_1}$  465,  $V_{\text{REF}_2}$  470, and  $V_{\text{REF}_3}$  475 to the comparators 450, 455, and 460. The reference voltages  $V_{\text{REF}_1}$  465,  $V_{\text{REF}_2}$  470, and  $V_{\text{REF}_3}$  475 are produced by the reference generator 400 from the reference current generators  $I_{\text{REF}_1}$  405,  $I_{\text{REF}_2}$  415, and  $I_{\text{REF}_3}$  425. The reference currents  $I_{\text{REF}_1}$ ,  $I_{\text{REF}_2}$ , and  $I_{\text{REF}_3}$  respectively flow through the load resistors  $R_{1_1}$  410,  $R_{1_2}$  420, and  $R_{1_3}$  430 to generate the reference voltages  $V_{\text{REF}_1}$  465,  $V_{\text{REF}_2}$  470,  $V_{\text{REF}_3}$  475. The reference current generators  $I_{\text{REF}_1}$  405,  $I_{\text{REF}_2}$  415, and  $I_{\text{REF}_3}$  425 reference current generators  $I_{\text{REF}_1}$  405,  $I_{\text{REF}_2}$  415, and  $I_{\text{REF}_3}$  425 are structured and operate as described for the reference generator 300 of Fig. 8.

[0053] In summary the process for generating multiple reference levels of this invention begins with providing nonlinear resistive elements such as magnetic

tunneling junctions to act as reference elements for the generation of the reference levels. Each resistive element is biased at a constant voltage or current level to impart a resultant current or voltage level from each resistive element. This resultant current or voltage level has a resistance that is a  
5 nonlinear function of the applied voltage or current. With the biased voltage as applied to each resistive element being equal to a sensing voltage for determining the stored contents of a memory employing similar resistive elements for the storage elements.

[0054] The resultant current or voltage level developed from each nonlinear  
10 resistive element is replicated to provide a mirrored replication current or voltage of the resultant current or voltage level from each resistive element. Two of the mirrored replication currents or voltages are effectively combined in a fashion to create each of the multiple reference levels. Normally the combination of the mirrored replication current or voltage levels set the reference level as a midpoint  
15 between the two mirrored replication current or voltage levels.

[0055] As described for the preferred embodiment, the constant level is a voltage across the resistive element (two MTJ's having particular magnetic orientations). The resultant level is a current from the constant voltage across the resistive element. The resultant current level is then mirrored. Two of the mirror current  
20 levels from two resistive elements (two set of two MTJ's, each having differing orientations) are added. The resulting sum current is then scaled to form the reference current level.

[0056] If the desired reference level is a voltage, the reference current flows through a provided reference resistor. The reference current flowing through the reference resistor develops the reference voltage.

[0057] While this invention has been particularly shown and described with  
5 reference to the preferred embodiments thereof, it will be understood by those skilled in the art that various changes in form and details may be made without departing from the spirit and scope of the invention.

[0058] The invention claimed is: